

LEELIS

4, 5 November 2014 Amsterdam

Low Energy Electrons: Lithography, Imaging and Soft matter

A forum for:

- **Microscopy**
- **EUV lithography**
- **Interaction with resist**
- **Industry and academia**

Confirmed speakers

- **Alex Robinson** (School of Chemical Engineering, Birmingham University, UK)
- **Aniket Thete** (Leiden Institute of Physics, Leiden University, NL)
- **Armin Götzhäuser** (Supramolecular Systems and Surface Physics, Bielefeld University, DE)
- **Diederik Maas** (Charged Particle Optics, Nano-Imaging and Fabrication, TNO, Delft, NL)
- **Hubertus Marbach** (Microscopy and Nanolithography, Erlangen University, DE)
- **Nigel Mason** (Molecular Physics, The Open University, UK)
- **Paul Alkemade** (Kavli Nanolab, TU Delft, NL)
- **Roel Gronheid** (Advanced Resist Technologies, IMEC, BE)
- **Rudolf M. Tromp** (Low Energy Electron Microscopy, IBM, Yorktown heights, NY, USA)
- **Willem van Dorp** (Zernike Institute for Advanced Materials, Groningen University, NL)

Start of the workshop: 4th November 2014. 09:00

End of workshop: 5th November 2014 12:30

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